

IN THE CLAIMS:

Please amend the claims as follows:

sub
D1
C1
28. (Amended) A belt comprising (a) a polishing surface for polishing a workpiece in a chemical mechanical linear polishing system and (b) a side opposite the polishing surface, the belt forming an endless loop, an improvement comprising at least one aperture from the polishing surface through the side opposite the polishing surface so that the aperture is substantially free of a window, the aperture positioned on the belt to allow monitoring of the workpiece through the aperture; and

a fluid platen adjacent the side opposite, said fluid platen comprising an aperture to allow a light beam to pass through the platen and onto the workpiece, the fluid platen operable to provide liquid and gas pressure to said platen aperture to clear a slurry from said aperture of said platen.

C2
38. (Amended) A belt comprising (a) a polishing surface for polishing a workpiece in a chemical mechanical linear polishing system and (b) a side opposite the polishing surface, the belt forming an endless loop, an improvement comprising at least one aperture from the polishing surface through the side opposite the polishing surface so that the aperture is substantially free of a window, the aperture positioned on the belt to allow monitoring of the workpiece through the aperture; and

a fluid platen adjacent the side opposite, said fluid platen comprising an aperture to allow a light beam to pass through the platen and onto the workpiece, the fluid platen operable to provide humidified air pressure to said platen aperture to clear a slurry from said aperture of said platen.

Please add new Claims 39-41, as follows

39. (New) A belt according to Claim 28, wherein said liquid and gas pressure is also directed to said belt aperture to prevent a slurry from draining through said belt aperture onto said platen.

40. (New) A belt according to Claim 38, wherein said humidified air pressure is also directed to said belt aperture to prevent a slurry from draining through said belt aperture onto said platen.

41. (New) A belt comprising (a) a polishing surface for polishing a workpiece in a chemical mechanical linear polishing system and (b) a side opposite the polishing surface, the belt forming an endless loop, an improvement comprising at least one aperture from the polishing surface through the side opposite the polishing surface so that the aperture is substantially free of a window, the aperture positioned on the belt to allow monitoring of the workpiece through the aperture; and a fluid platen adjacent the side opposite, said fluid platen comprising an aperture to allow a light beam to pass from a monitor through the platen and onto the workpiece, said fluid platen operable to provide a suction to said platen aperture to clear a slurry from said aperture of said platen.

REMARKS

Upon entry of this Amendment, claims 1-7 and 24-41 will be pending in the application. New claims 39-41 are supported by the specification. No new matter has been added.

The Rejection of the Claims Under 35 U.S.C. § 103

1. Claims 1-7 and 24-38 stand rejected under 35 U.S.C. 103(a) as being unpatentable over Dudovicz et al. (WO99/06182), in view of Birang (EP 0 738 561 A1), in further view of Engdahl et al. This rejection is respectfully traversed.